Agenda

Welcome	Namlab Dresden	09:00	T. Mikolajick/U. Schröder
MIM Capacitor			
1) STO/SRO	RWTH Aachen	09:15	S. Schmelzer
2) STO/Ru	University Helsinki	09:35	J. Niinistö
3) TiO/Ru	University Bratislava	09:55	K. Fröhlich
4) Liquid Injection ALD of TiO_2 Films and Resistive Switching Effect in thin TiO_2	FZ Jülich	10:15	S. Hoffmann-Eifert
Break		**10:45**	

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MIM Capacitor

5) Ferroelectric HfO_2- and ZrO_2-based thin films for non-volatile memory applications
CNT/Aachen/Namlab 11:05 J. Müller/D. Bräuhaus

6) Characterization of High-k Dielectrics by SPM Technique
IISB Erlangen 11:25 A. Bauer

7) ALD of ZrO_2:Gd_2O_3 and ZrO_2:Er_2O_3 thin films and nanolaminates
University Helsinki 11:45 K. Kukli

8) MIM Progress at IHP: Status and future activities
IHP Frankfurt/Oder 12:05 C. Weger

9) Preparation and Characterization of thin $CaTiO_3$ layers
Namlab Dresden 12:25 A. Krause

Lunch MPI Cantine 12:40

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Process

10) Strontium Titanate thin films deposited by Atomic Layer Deposition	CNT/IKTS	14:00	S. Riedel
11) ALD of Ir and Ir-O using Ir(EtCp)(COD) and O_2	IHM TU Dresden	14:20	C. Hossbach
12) Low temperature Al_2O_3 ALD	Namlab/IHM	14:35	E. Erben
13) ZrO MBE	Namlab Dresden	14:50	M. Grube

Leakage/Reliability/Characterization

14) ALD Insitu charact.	IHM TU Dresden	15:05	M. Knaut
Break		**15:20**	

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15) Process chemistry of TiO_2 and HfO_2 ALD	IKTS Dresden	15:40	M. Rose
16) Atom probe of ZrO MIM	FhG CNT Dresden	16:00	A. Shariq
17) cAFM on ZrAlO	Namlab Dresden	16:15	D. Martin
18) ZrO_2 – Modeling of leakage current via kinetic Monte Carlo	TU Munich	16:30	G. Jegert/A.Kersch
19) Reliabilty of $Zr_xAl_yO_2$ high-k dielectrics in 3D MIM capacitors	Namlab Dresden	16:50	D. Zhou
End		**17:05**	